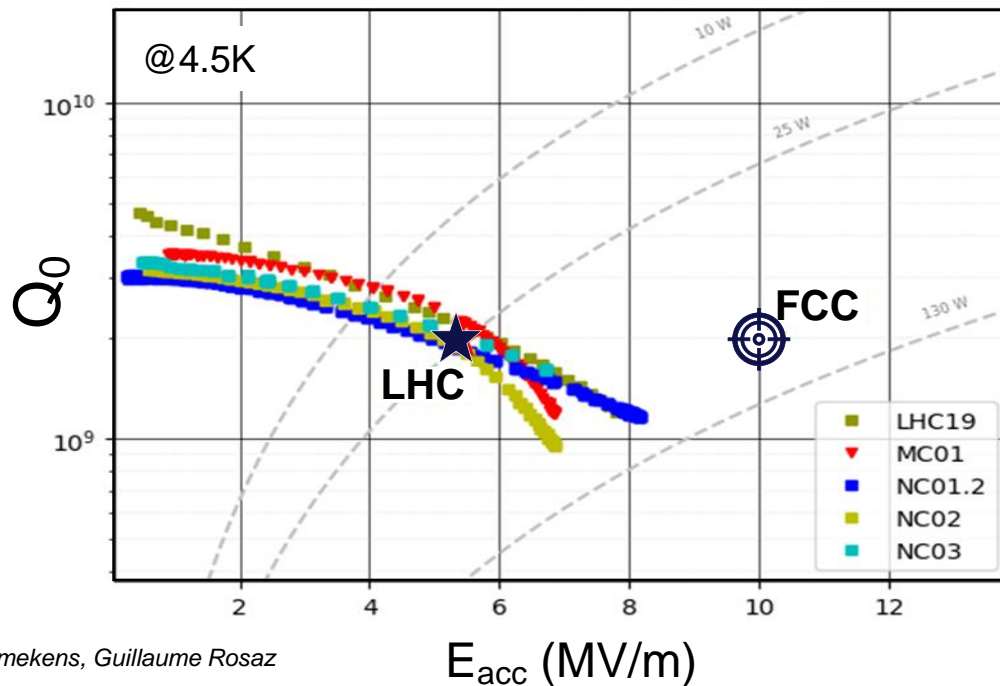


Nb/Cu thin film HiPIMS coatings optimization for SRF applications

C. P. A. Carlos, S. Leith, G. Rosaz, M. Bonura, C. Senatore, S. Pfeiffer, A. Teresa Perez Fontenla, M. Taborelli

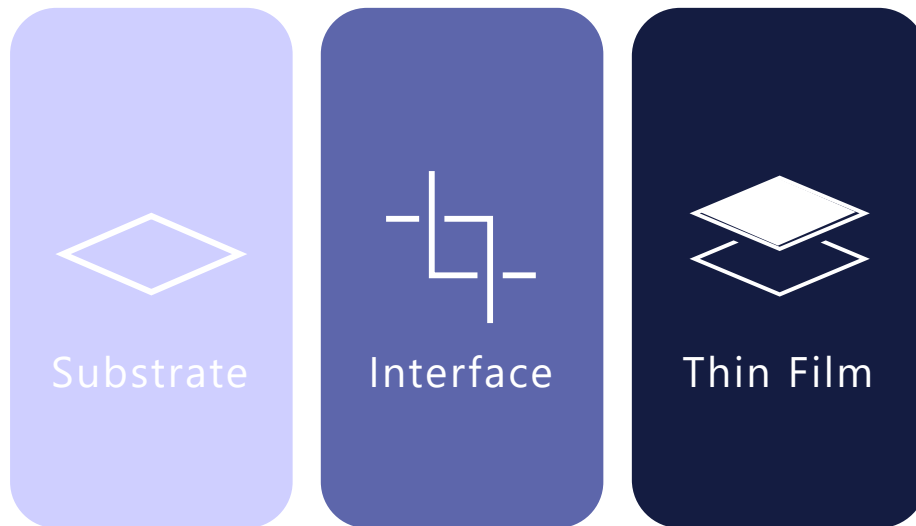
MOTIVATION

400MHz LHC cavities spares: last results

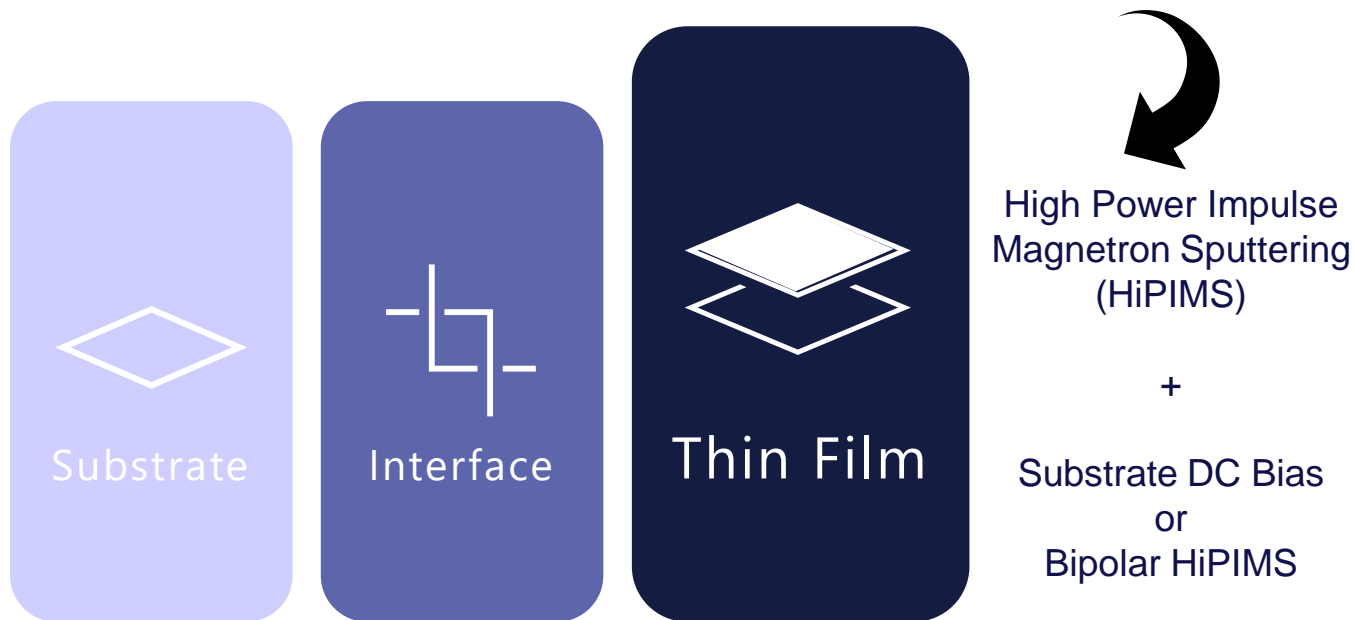


$E_{acc} = 10$ MV/m
 Q_0 above 2×10^9
 @4.5 K

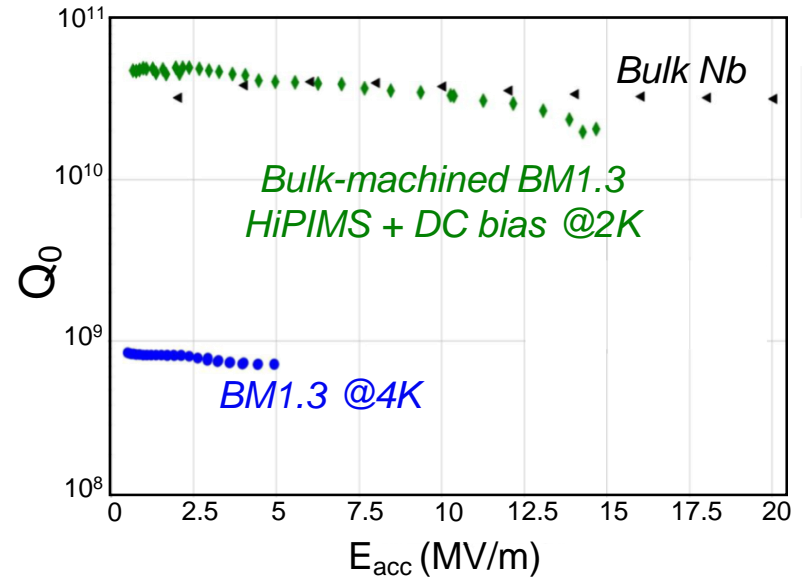
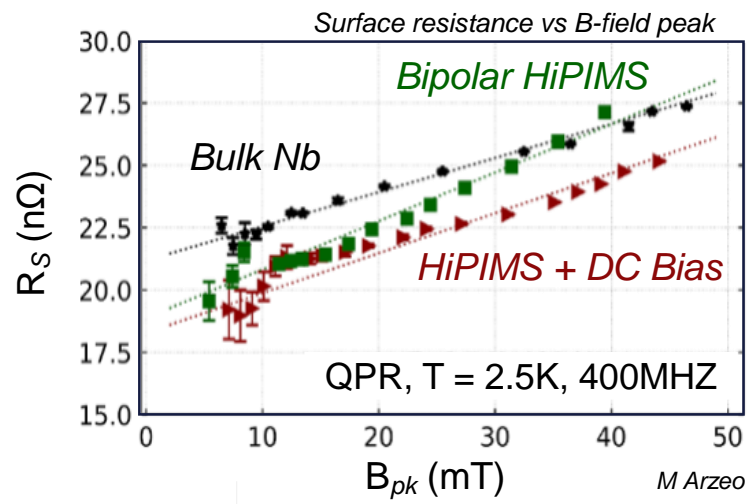
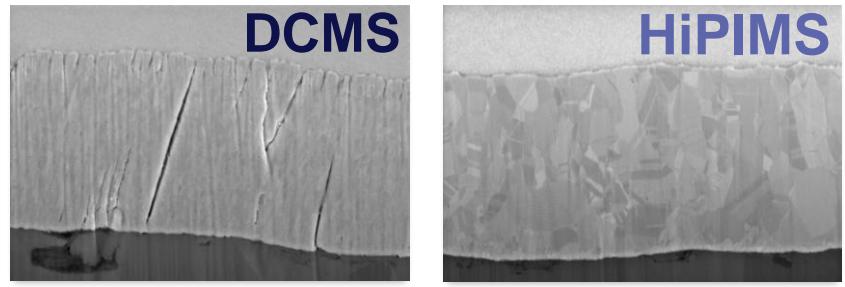
R&D axis of research at CERN to improve the performance of SRF cavities

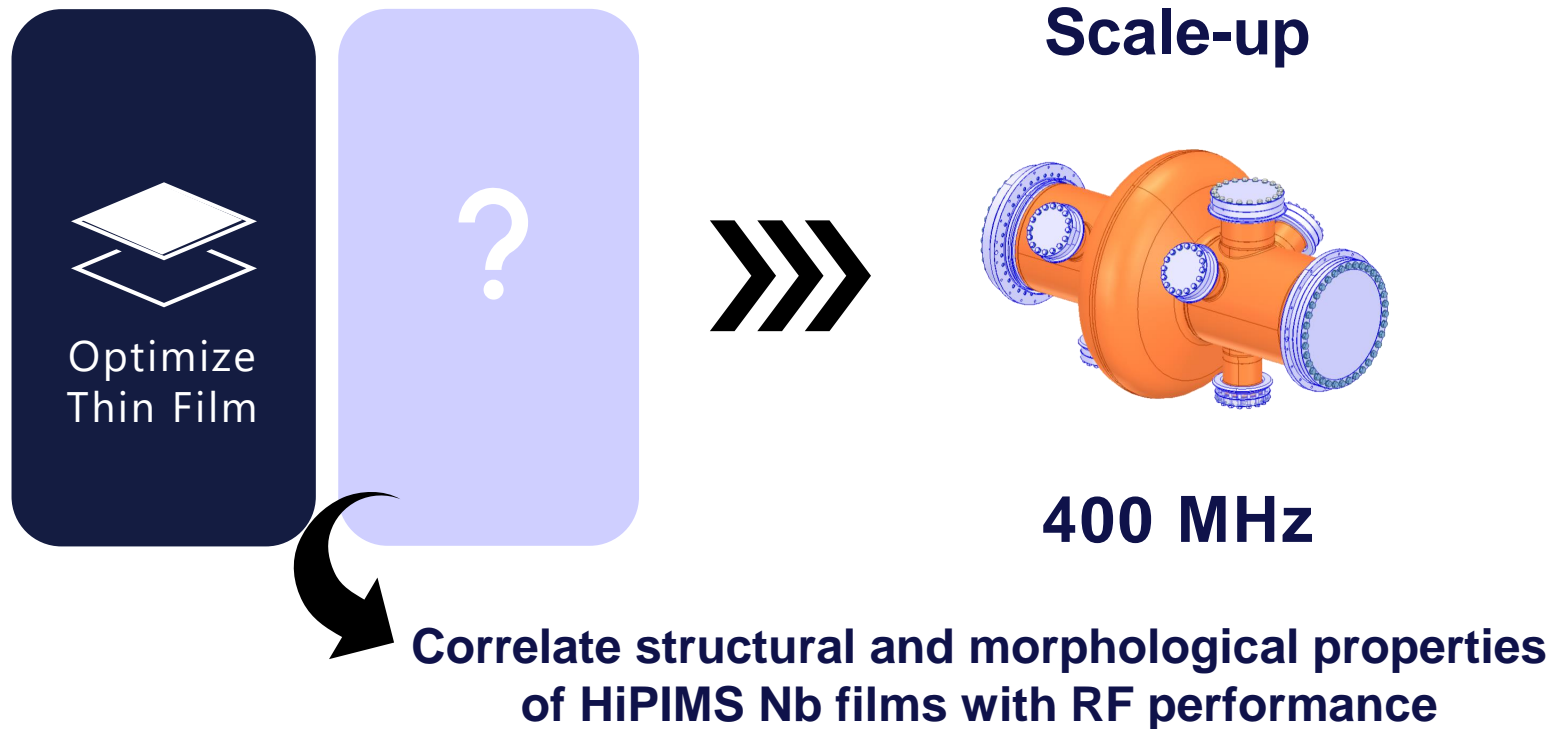


Optimization of thin film Nb/Cu coatings



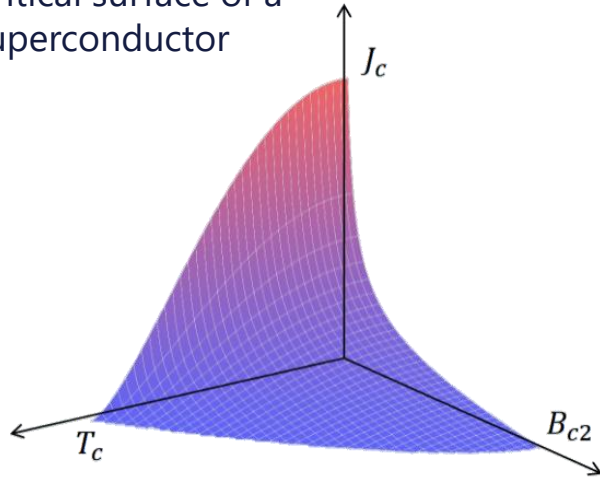
Why HiPIMS?





CRITICAL CURRENT DENSITY J_c

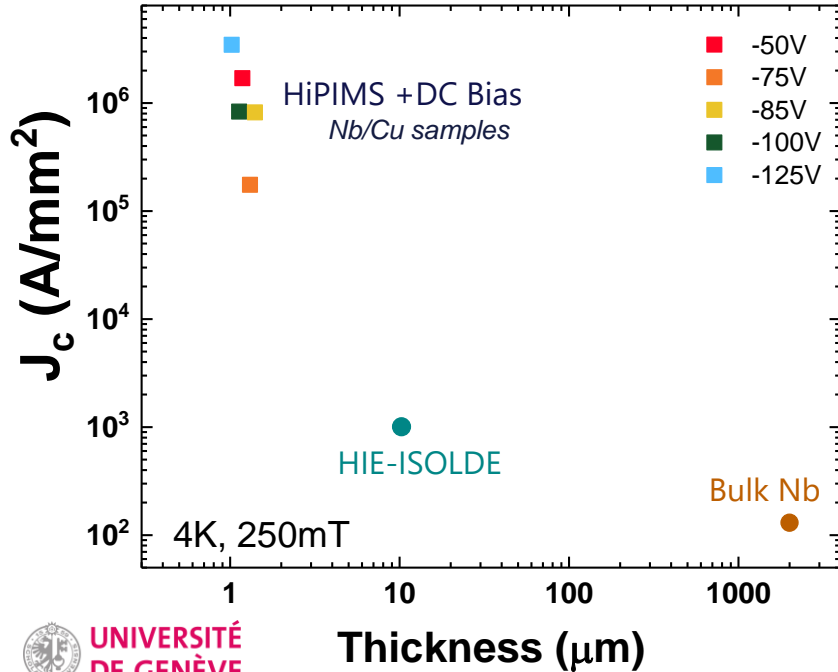
Critical surface of a superconductor



- Used to qualify the performance of superconductors, especially for magnets
- Depends on pinning centres (structural defects) – Lower J_c translates into a layer with less defects

CRITICAL CURRENT DENSITY J_c

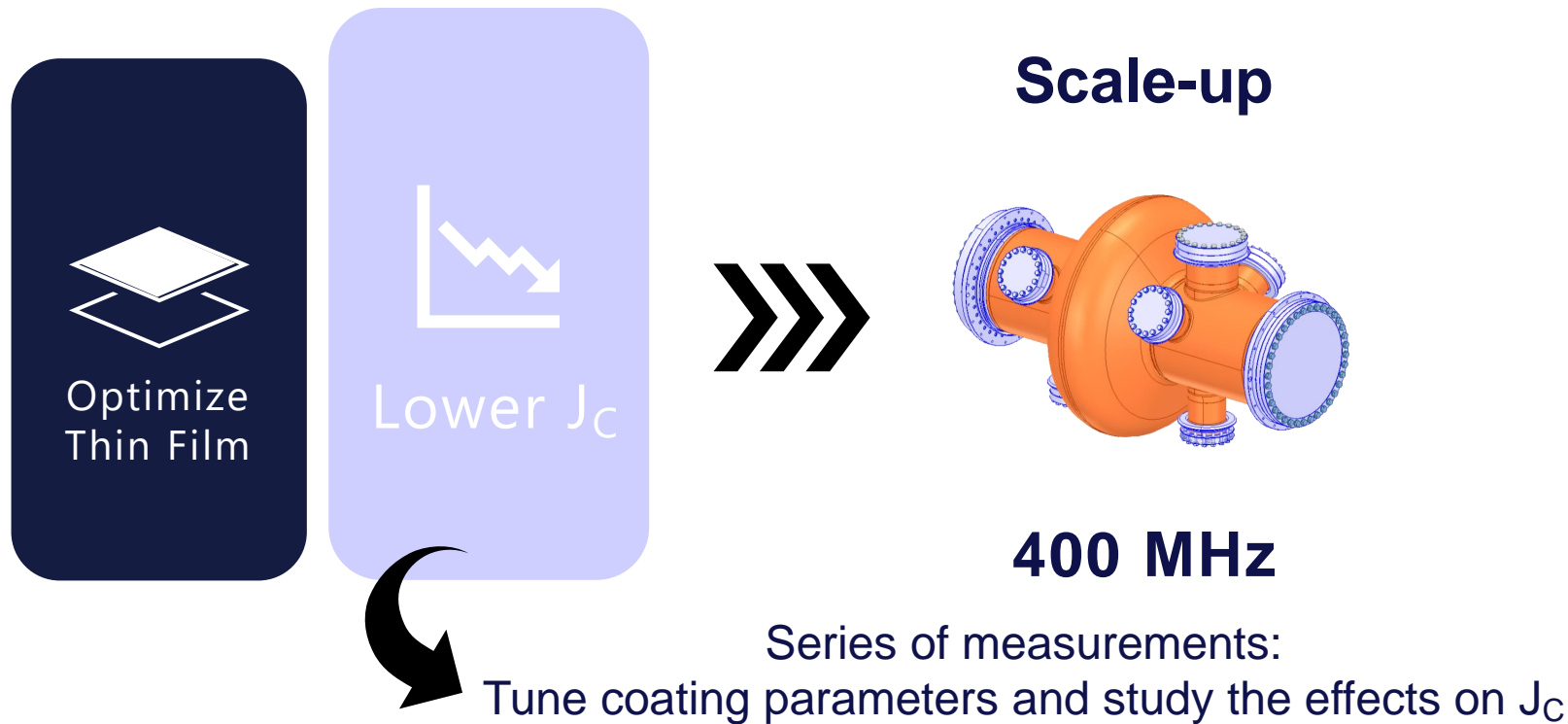
Where are we?



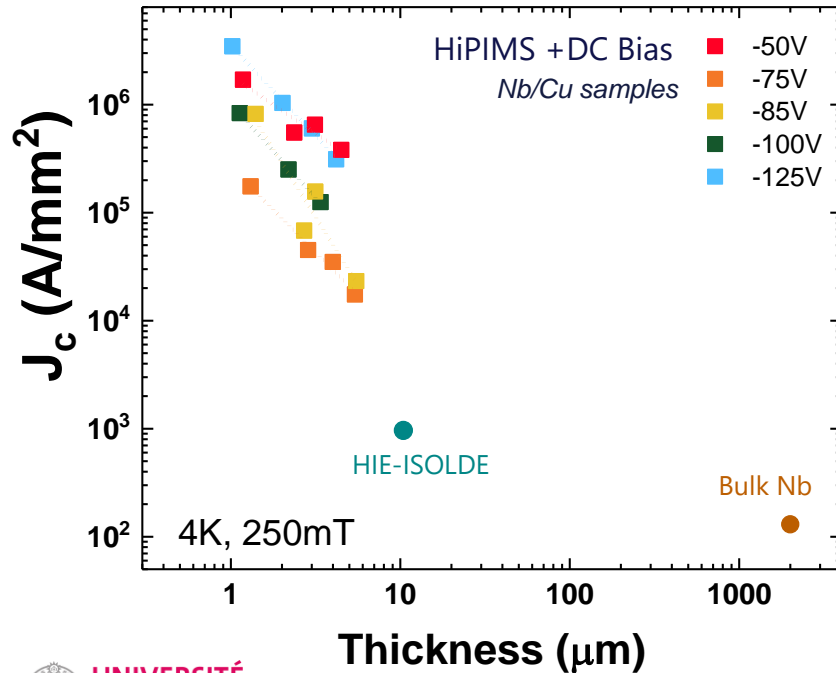
J_c of our HiPIMS samples is orders of magnitude higher than HIE-ISOLDE (E_{acc} up to 120mT, corresponding to $\sim 30\text{MV}/\text{m}$ in an elliptical cavity) and Bulk Nb (E_{acc} up to 49 MV/m with $Q_0 > 10^{10}$)

Lower J_c seems to result in better RF performance

There's room for improvement in our films



THICKNESS vs J_c



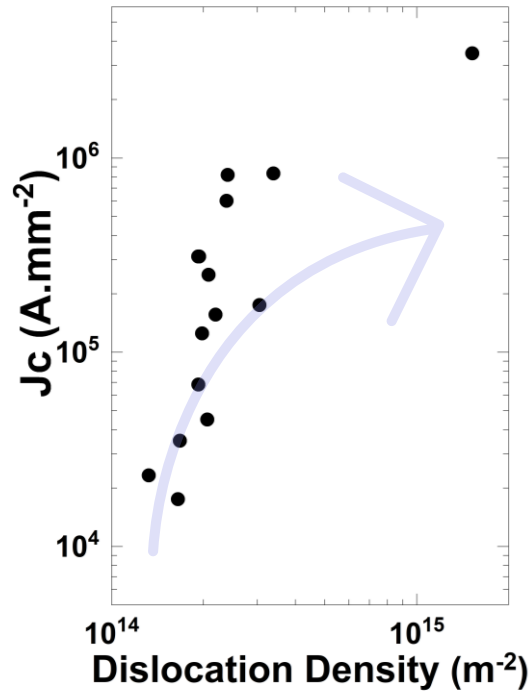
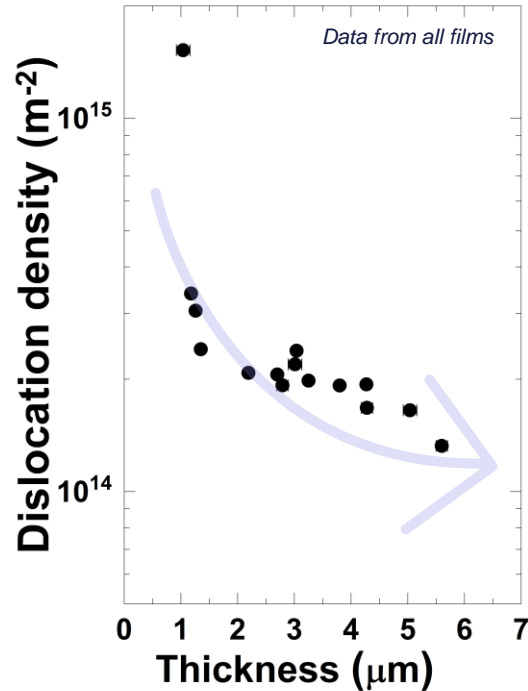
J_c decreases with
 increasing film thickness
 Independently of bias



What morphological property
 is responsible for this?

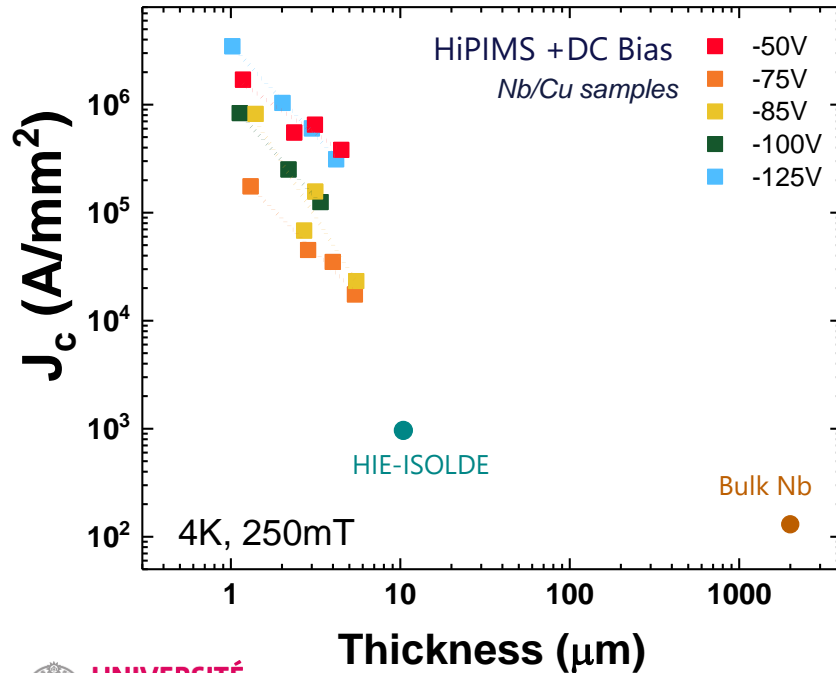
i. e. which defect family disappears gradually
 with increasing thickness?

DISLOCATION DENSITY vs J_c



Dislocations seem to be driving defects for J_c optimization

ION BOMBARDMENT ENERGY vs J_c



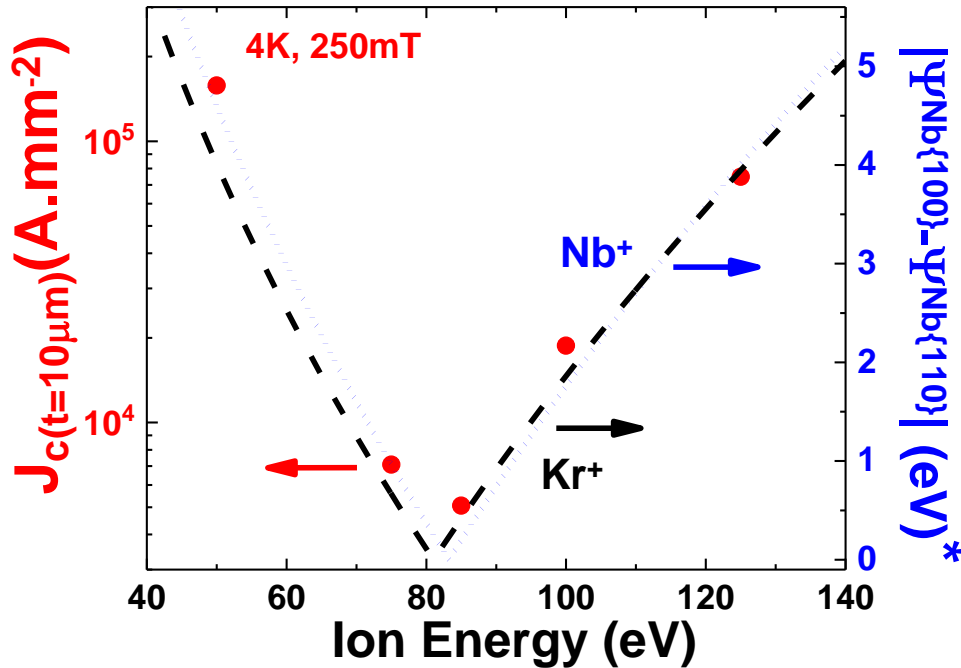
Bias voltage applied corresponds to the ion energy impinging the surface

$$E_{ion} = |eV_B|$$

Nonlinear relation:

**optimum J_c with
-80V applied DC bias**

ION BOMBARDMENT ENERGY vs J_c



Optimum J_c when the energy is equally spread among the $\{100\}$ and $\{110\}$ crystalline planes

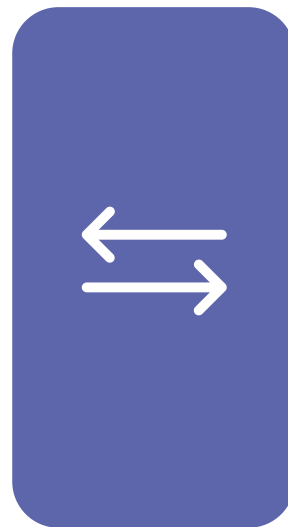
* binary collision approximation [1][2]

[1] D. K. Brnce et al. *Nuclear Instruments and Methods in Physics Research*, 44 1989 68-78

[2] Z.Q. Ma et al. *Applied Surface Science* 137 1999 184-190M

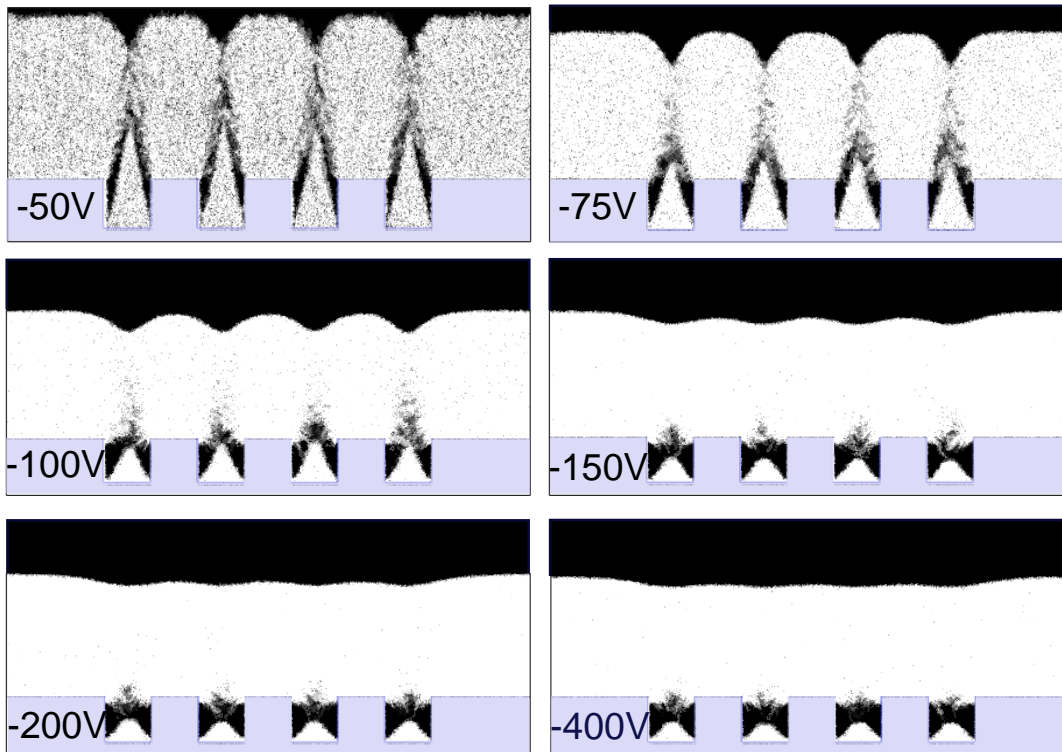
Optimization of thin film Nb/Cu coatings

Relax substrate
quality
requirements



Can we planarize a layer deposited on a very rough substrate with HiPIMS?

Nb PLANARIZATION



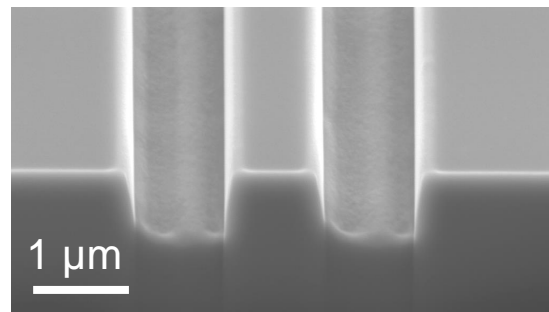
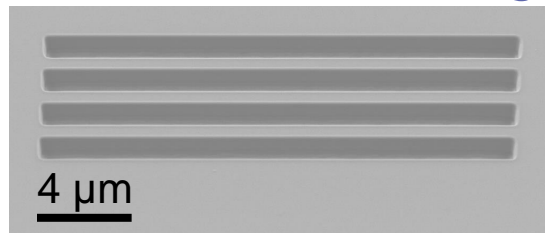
Planarization vs substrate DC bias

NASCAM simulations

Textured Si substrate
No surface diffusion (thermal effects neglected)
100% ionized Nb
Impinging angle: $(90 \pm 10)^\circ$

Nb PLANARIZATION

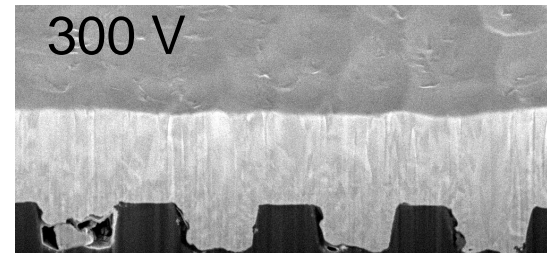
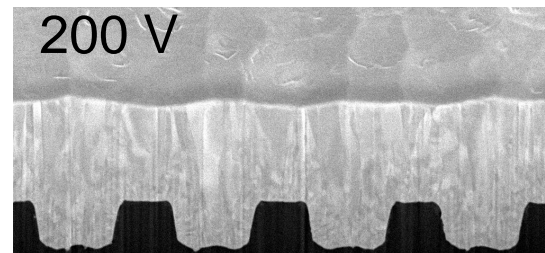
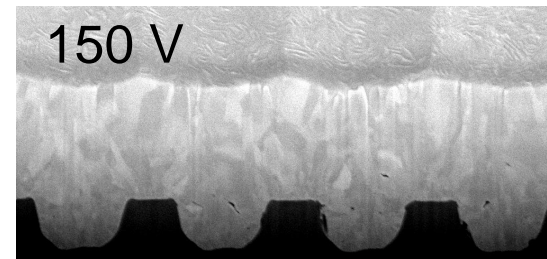
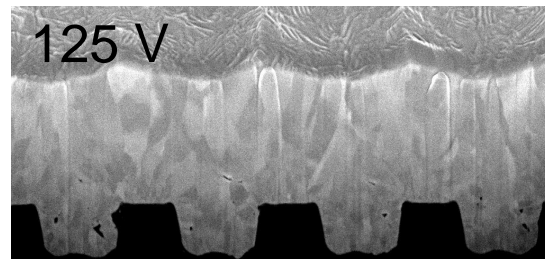
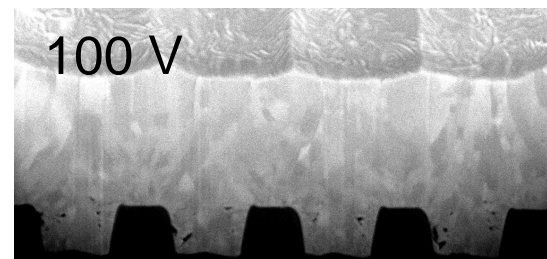
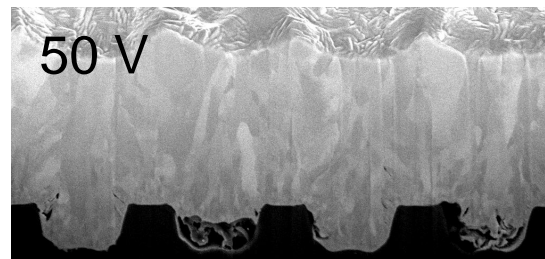
FIB milling



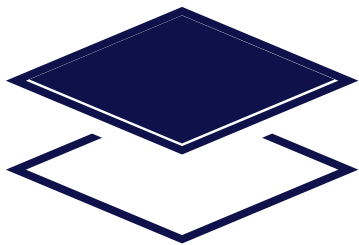
Si samples w/ 1x1x20 μm trenches

HiPIMS + substrate DC bias

1 μm



FUTURE WORK



J_c



Post coating annealing



Coating temperature



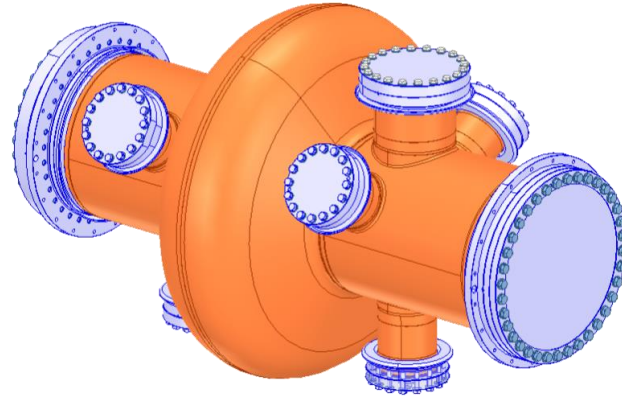
Substrate treatment

Nb planarization

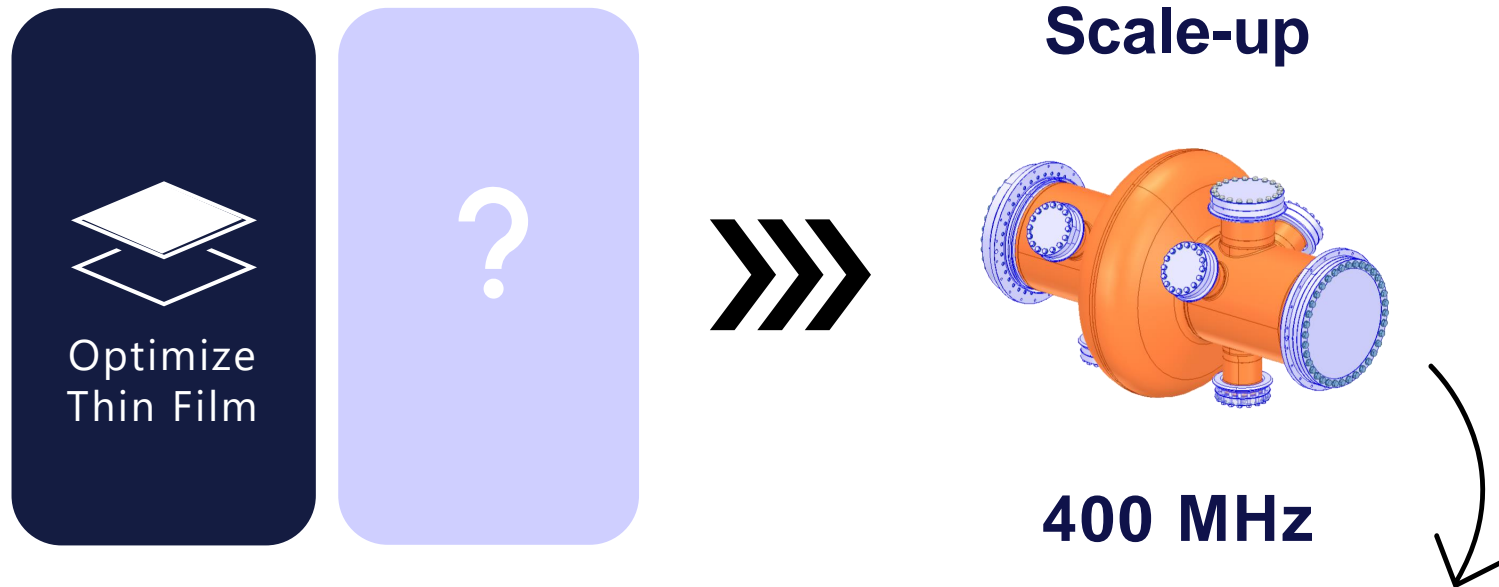


Coating Cu cavity first with a very thin Nb layer at high bias and then coat rest of the layer with optimal HiPIMS recipe

Scale-up HiPIMS

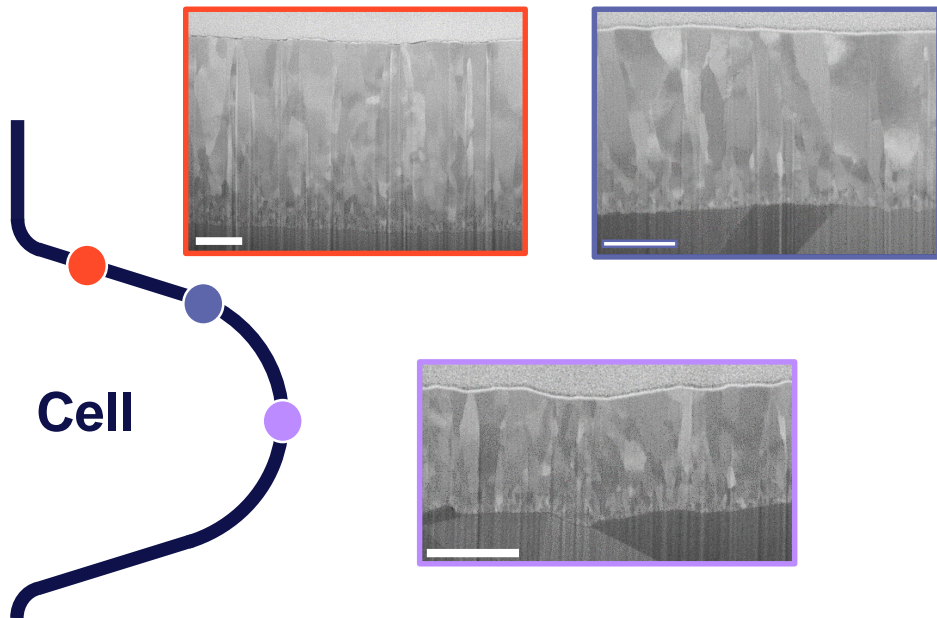


400 MHz cavities



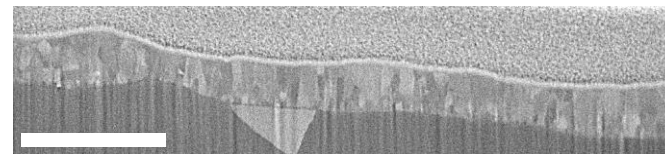
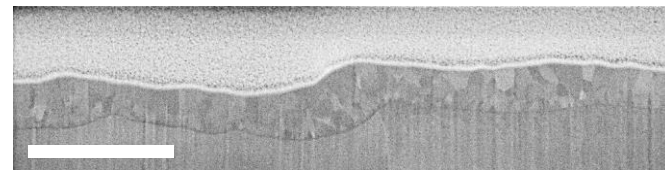
HiPIMS + substrate DC bias not yet possible
Bipolar HiPIMS compatible with current setup

400 MHz ACTIVITIES



Coating densification

BIPOLAR HiPIMS
(+80V)
 coating trial on samples



HOM ports

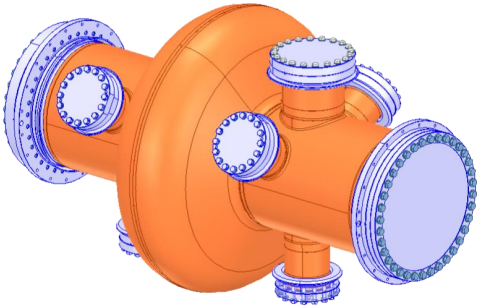
400 MHz ACTIVITIES

**1st BIPOLAR
HiPIMS cavity
coating on 05/2022**

RF performance to be measured
June/July 2022



FUTURE WORK



BIPOLAR HiPIMS

- RF performance of 1ST test cavity to be measured
- Optimize coating setup and parameters

HiPIMS + DC bias

- Proven on 1.3GHz
 - Lot of RF data
- More complex coating setup
 - Upgraded cathode under study
 - Grid like anode needed + cavity insulation

- 3 RF tests / year foreseen



Thank you for your attention!